

AMENDMENTS TO THE SPECIFICATION

Please replace the paragraph at page 1, lines 5-15, with the following amended paragraph:

The present application is related to the following commonly owned U.S. Patent Applications, incorporated in their entirety herein by reference:

U.S. Patent Application No. 10/606,463 filed June 26, 2003, entitled "USE OF I²C-BASED POTENTIOMETERS TO ENABLE VOLTAGE RAIL VARIATION UNDER BMC CONTROL," naming as inventors Benjamin T. Percer, Naysen J. Robertson and Akbar Monfared (~~Attorney Docket No.: 200208051-1~~); U.S. Patent Application No. 10/606,715 filed June 26, 2006, entitled "METHODS AND SYSTEMS FOR MASKING FAULTS IN A MARGIN TESTING ENVIRONMENT" naming as inventors Benjamin T. Percer and Naysen J. Roberston (~~Attorney Docket No.: 200312936-1~~); and U.S. Patent Application No. 10/606,713 filed June 26, 2003, entitled "USE OF I²C PROGRAMMABLE CLOCK GENERATOR TO ENABLE FREQUENCY VARIATION UNDER BMC CONTROL," naming as inventors Naysen J. Robertson, Benjamin T. Percer, and Kirk Yates (~~Attorney Docket No.: 200208055-1~~).

Please replace the paragraph at page 1, lines 23-33, with the following amended paragraph:

Electronic systems often include a myriad of subsystems and components that require monitoring and/or testing during development and/or [[,]] manufacturing ~~and/or~~ while in use in the field to ensure their proper operation within specified operating conditions. Many of these components typically exhibit subtle failures at margins or extremes of such specified operating conditions. Hence, it is desirable to test a system to variations of operating conditions, such as, ambient temperature, clock frequencies and power rail voltages, associated with selected components thereof, during development and manufacturing, to ensure system reliability. Such testing of a system, especially at the extremes or margins of the operating conditions, is herein referred to as margin testing. Margin testing can also ensure that a particular design can be readily adapted to evolving changes in manufacturing processes.